Supplementary Files

Nonvolatile modulation of electronic structure and correlative magnetism of L1₀-FePt films using significant strain induced by shape memory substrates

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Figure S1



Figure S1 Dynamic thermomechanical analysis (DMA) curves of the pure SMA substrates. (a) Pre-loading 6%, recoverable macro-strain ϵ_{M} = -2.7%; (b) Pre-loading 8%, ϵ_{M} = -3.5%; (c) Pre-loading 10%, ϵ_{M} = -5.0%; (d) Pre-loading 12%, ϵ_{M} = -5.5%.

Figure S2



Figure S2 In-plane (along the strain) and out-of-plane hysteresis loops of the lattice strain treated

L1₀-FePt(10 nm) film. (a) ϵ_L = 0%; (b) ϵ_L = -0.48%; (c) ϵ_L = -0.78%; (d) ϵ_L = -1.63%; (e) ϵ_L =

-2.18%.





Figure S3 In-plane (along the strain) and out-of-plane hysteresis loops of the lattice strain treated

L1₀-FePt(15 nm) film. (a) ϵ_L = 0%; (b) ϵ_L = -0.48%; (c) ϵ_L = -0.78%; (d) ϵ_L = -1.63%; (e) ϵ_L =

-2.18%.

Figure S4



Figure S4 In-plane (along the strain) and out-of-plane hysteresis loops of the lattice strain treated

L1₀-FePt(20 nm) film. (a) ϵ_L = 0%; (b) ϵ_L = -0.48%; (c) ϵ_L = -0.78%; (d) ϵ_L = -1.63%; (e) ϵ_L =

-2.18%.

Figure S5



Figure S5 First-principles calculation results for larger strains ranging from 0% to 5%. (a) DOS of spin-up (\uparrow) and spin-down (\downarrow) electrons in L1₀-FePt films, the dashed line stands for Fermi level. When ε_L =-5%, the spin distribution shift by 0.5eV comparing with the ε_L =0% case. (b) Variations of magnetic moment (MM) and total SOC strength (ξ_{total}) with ε_L . The ξ_{total} increases from 746 meV (ε_L = 0%) to 769 meV (ε_L = -5%) with a considerable variation of 23 meV.

Figure S6



Figure S6 Variations of experimental magnetization in strain treated L1₀-FePt films with ϵ_{L} . *t* represents the thickness of the L1₀-FePt layer.